

SEMICON[®] KOREA



Product Portfolio

PECVD

SiON	SiO ₂	SiN	a-Si	High Thick TEOS
SiOC	SiCN	TEOS	FTEOS	

PEALD

ALD OX	TiO ₂	SiN
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Metal

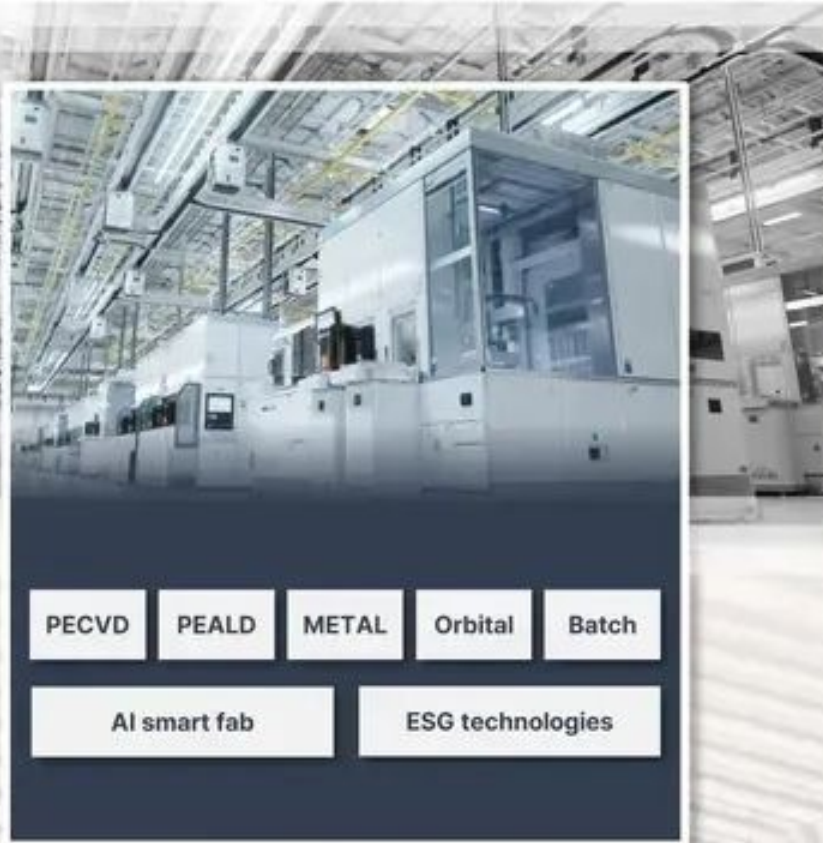
CVD	Ti/TiN	W	SGW
ALD	TiN	W	TiSiN

Orbital

ZrO	AlO	O ₃	HfO	MOCVD (GaN)
SiN	SiGe	SiO ₂	SiP	

Batch

SiN	SiO	SiON	TiO ₂
H2 Alloy	PI Bake	Poly	



PECVD PEALD METAL Orbital Batch

AI smart fab

ESG technologies

AI Smart fab

equipped with AI technology for Industry 5.0 and provides continuous solutions

***AI Based PHM**
Prognostic and Health Management

Autonomous Robot

R&D Accelerator Solution

World-Class TEOS

Logic Device

Advanced Stress, Uniformity & Defect Control capability

Advanced Packaging

Wider Temp. management system with advanced Warpage control

Silicon Photonics

High Quality TEOS with better R.I control

WONIK IPS Key Benefit

Enables 1-shot Deposition up to 12µm

Multi-shot depo VS 1-shot depo
(WONIK IPS)

>30% Improvement

We Make Net Zero

FACTORY Carbon Reduction 25%
PRODUCT Carbon Reduction 20% in 2030
Net ZERO in 2050

Replacing High GWP
(NF₃ ▶ New Clean Gas)

+

Additional Carbon
Emissions Reduction Solution

New Clean Gas Property

F contents
(F, F₂, HF)

96%

Etch Rate
(on SiO₂, SiN)

97%

· Already proved to be a good clean gas source

· WONIK IPS offers an unique clean solution package to match POR clean etch rate